

Notice of References Cited

Application/Control No.

09/901,917

Applicant(s)/Patent Under

Reexamination

WALKER ET AL.

Examiner

Toniae M. Thomas

Art Unit

2822

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,064,683	11-1991	POON et al.	427/569
	B	US-5,872,045	02-1999	LOU et al.	438/432
	C	US-			
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	K	US-			
	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, Ph.D., Stanley, Richard N. Tauber, "Thermal Oxidation of Single Crystal Silicon," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, page 198.
	V	Wolf, Ph.D., Stanley, Richard N. Tauber, "Chemical Vapor Deposition of Amorphous and Polycrystalline Films," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, page 181-182.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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